

A STATE		سلتنظ بالسنال ك	8 21 44	9/4/9		Nie . S				
	ding				Estrofi Jun Browies Queue	Clear	\$ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\		- 100	26 00
	ive				Secret Green	Seat 1	Market State Comment		* / 7X	2.1
	U 🗫 Do	cument II	D Issue Da	Page	Title (Current	OR Current XR Re	trieval 🌲 . Inventor 💸	S	C
5	n n US	6080622	20000627	6	Method for fabricating	438/253	257/306;	Kang, Woo-Tag	P	
24 .	Δ		:	1	a DRAM cell capacitor		257/E21.64			
	D D US	6078493	20000620	17	Fin-shaped capacitor	361/303	257/308;	Kang, Chang-seok	2	10
᠍.	A			<u> </u>		1	257/310;			
		60/1//3	20000606	13	Process for	438/253	438/235;	Lee, Jin-Yuan et	₽.	10
		6066543	100000505	110	fabricating a DRAM met		438/238;	al.		
	B DUS	6066541	20000523	12	Method for fabricating		257/E21.01	Hsieh, Ming-Teng	П	
	- A	COCCEDO	20000523	122	a cylindrical capacito			et al.	- <u>-</u>	
	B D OS	6066528	20000523	32	1	438/253	257/E21.01	Fazan, Pierre C.		10
× -	A	6060353	20000509		capacitor compatible w	438/253	257/E21.01	et_al.		-
	S 12 02	9090333	20000309	13	Method of forming a			Koh, Chao-Ming	D	10
	H	6060351	20000509	1 /	ring shaped storage no Process for forming	438/253	6; 257/E21.64	Parekh, Kunal R.		
	P ID US	0000331	20000309	14	capacitor over bit lin		1		n	
	IIC	6054347	20000425	16	Method for forming a	438/253	6 <i>i</i>	et al. Lin, Chin-Hsiang		
	Z L	0034347	20000425	10	modified crown shaped,			bill, Chill-halang	0	15
	IIC	6046083	20000404	110		438/255	257/E21.01	Lin, Dahcheng et		+
	S 12 /2	0040003	20000404	10	hemispherical grain si		2;	, ,	С	0
	IIS	6034392	20000307	21	Semiconductor device	257/306	257/532;	Joo, Jae-Hyun		+
	S D Y	0034332	20000307		having capacitor	2377300	257/534;	Jooo, Jae-Hyun	D	ĺ
	IIS	6025247	20000215	26	Method for	438/396	257/E21.64	Chang, Julian Y.		+
*	Δ		i	1	manufacturing capacito		8:	et al.	П	
	- US	6025227	20000215	13	Capacitor over bit	438/253	257/306;	Sung, Janmye		1
	Δ:		!	1	line structure using a	,	257/E21.64	Dang, James		C
	- US	6020248	20000201	18	Method for fabricating		257/E21.01	Zenke, Masanobu		1
	: A		1	•	semiconductor device h		3;			D
	US	6015734	20000118	12	Method for improving	438/253	257/E21.64	Huang, Kuo Ching		1_
	A				the vield on dynamic r		8;	et al.	П	12
	, LUS	6010942	20000104	10	Post chemical	438/396	257/E21.01	Chien, Rong-Wu e	t o	
	Δ			1	mechanical polishing.	1	2;	al.	1.3	
	US	6008085	19991228	13	Design and a novel	438/253	257/E21.64	Sung, Janmye et	C	Б
	Δ		1	!	process for formation	<u> </u>	8;	al.	1 1.3]]
	US	5989954	19991123	11	Method for forming a	438/253	257/E21.64	Lee, Yu-Hua et	T 6	6
	Δ		:		cylinder capacitor in	!	8;	al	;	
	US	5972770	19991026	15	Method of	438/396	438/253	Hsu, Chen-Chung	Г	Б
<u>.</u>	A		1	1	manufacturing a DRAM c					1.,
	US	5960280	19990928	12	Method of fabricating	438/254	257/E21.01	Jeng, Jason et	П	Б